

Amendments to the Claims

Claims 1-10 (Cancelled).

11. (Currently amended): A boron and/or phosphorus doped silicon dioxide selective to undoped SiO₂ and Si₃N₄ etchant gas composition, consisting essentially of:
a carrier gas;
at least one of C₄F₆ and C₅F₈;
CH₂F₂; and
CF₄, the etchant gas composition being constituting a boron and/or phosphorus doped silicon dioxide selective to both undoped SiO₂ and Si₃N₄ etchant gas composition relative to doped SiO₂ comprising one or both of boron and phosphorous.

Claims 12 and 13 (Cancelled).

14. (Original): The etchant gas composition according to Claim 11, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

15. (Previously Presented): The etchant gas composition according to Claim 11, wherein the carrier gas comprises argon.

16. (Previously presented): A boron and/or phosphorus doped silicon dioxide selective to undoped SiO₂ and Si₃N₄ etchant gas composition, consisting essentially of:

a carrier gas;

at least one of C₄F₆ and C₅F₈;

CH₂F₂;

CHF₃; and

CF₄ constituting a boron and/or phosphorus doped silicon dioxide selective to undoped SiO₂ and Si₃N₄ etchant gas composition.

Claims 17 and 18 (Cancelled).

19. (Original): The etchant gas composition according to Claim 6, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

20. (Previously Presented): The etchant gas composition according to Claim 16, wherein the carrier gas comprises argon.

Claims 21-68. (Cancelled).

69. (Previously Presented): The etchant gas composition according to Claim 11 wherein the carrier gas comprises helium.

70. (Previously Presented): The etchant gas composition according to Claim 16 wherein the carrier gas comprises helium.

Claims 71- 72 (Cancelled).

73. (Previously Presented): The etchant gas composition according to Claim 11 wherein the carrier gas comprises xenon.

74. (Previously Presented): The etchant gas composition according to Claim 16 wherein the carrier gas comprises xenon.

Claims 75-80 (Cancelled).

81. (Previously Presented): The etchant gas composition according to Claim 11, comprising C₄F₆.

Claim 82 (Cancelled).

83. (Previously Presented): The etchant gas composition according to Claim 11, comprising C₅F₈.

84. (Previously Presented): The etchant gas composition according to Claim 16, comprising C₄F₆.

Claim 85 (Cancelled).

86. (Previously Presented): The etchant gas composition according to Claim 16, comprising C₅F₈.